TITLE OF THE INVENTION

SOLID-STATE IMAGING DEVICE

CROSS-REFERENCE TO RELATED APPLICATIONS

This application is based upon and claims the benefit of priority from the prior Japanese Patent Application No. 11-375475, filed December 28, 1999, the entire contents of which are incorporated herein by reference.

BACKGROUND OF THE INVENTION

The present invention relates to an amplification type solid-state imaging device for amplifying and extracting signals obtained by photoelectric conversion means, and especially a pixel signal readout driving circuit of CMOS type image sensor, which can be used for video cameras, electric still cameras or the like capable of electronic shutter control operation.

In recent years, the amplification type CMOS image sensor, known as solid-state imaging device appropriate for the application to video cameras, electric still cameras or the like, has a structure to amplify and extract signals obtained by the photoelectric conversion means for each cell by a MOS transistor. To be more specific, the charge detection node reads out the signal charges generated by the photoelectric conversion means, and the pixel cell itself is provided with the amplification function, by amplifying the potential of the detection node with the amplification

transistor inside the pixel cell.

Such CMOS image sensor is still more expected, because it is highly sensitive and appropriate for minimization of the pixel by the increase of pixel number or reduction of the image size, in addition to its low power consumption.

FIG. 9 shows schematically a configuration of conventional 330 thousands pixel amplification type CMOS image sensor provided with a readout circuit capable of reading out a pixel signal for every one pixel.

In FIG. 9, the imaging region A includes unit cells 1 of one pixel/one unit arranged in a matrix of rows and columns. Each unit cell 1 is composed of, for instance, four transistors Ta, Tb, Tc, Td and one photodiode PD. In other words, each unit cell 1 comprises a photodiode PD that a ground potential is applied to its anode, a readout transistor (shutter gate transistor) Td whose one end is connected to the cathode of the photodiode PD, an amplifying transistor Tb whose gate is connected to the other end of the readout transistor Td, a vertical selection transistor (row selection transistor) Ta whose one end is connected to one end of the amplifying transistor Td, and a reset transistor Tc whose one end is connected to a gate of a amplifying transistor Tb.

In addition, the imaging region A comprises a readout line 4 connected in common to the gate of each

readout transistor Td of the unit cell 1 in the same
row, a vertical selection line 6 connected in common to
the gate of each vertical selection transistor Ta of
the unit cell 1 in the same row, and a reset line 7
5   connected in common to the gate of each reset
transistor Tc of the unit cell 1 in the same row, in
correspondence to each pixel row.

Further, the imaging region A includes a vertical
signal line VLIN connected in common to the other end
10   of each amplifying transistor Tb of the unit cell 1 in
the same column, and a power supply line 9 connected in
common to the other end of each reset transistor Tc and
to the other end of respective vertical selection
transistor Ta of the unit cell 1 in the same column, in
15   correspondence to each pixel line.

Arranged in a horizontal direction in a first
external region (not shown) of the imaging region A are
a plurality of load transistors TL each of which is
connected between each one end of the vertical signal
20   line VLIN and the ground node to which gate a bias
voltage VVL is applied.

Moreover, a plurality of noise canceller circuits
composed, for instance, of two transistors TSH, TCLP
and two capacitors Cc, Ct are arranged in the
25   horizontal direction, in the second external region
(not shown) of the imaging region A. And, a plurality
of horizontal selection transistor TH connected to

respective other end of the vertical signal line VLIN
through the noise canceller circuit are arranged in the
horizontal direction.

Further, a horizontal signal line HLIN is

5 connected in common to the other end of the horizontal
selection transistor TH, and a horizontal reset
transistor (not shown) and an output amplification
circuit AMP are connected to the horizontal signal line
HLIN.

10 Here, the respective noise canceller circuit is
comprised of a sample hold transistor TSH whose one end
is connected to the other end of the vertical signal
line VLIN, a coupling capacitor Cc whose one end is
connected to the other end of the sample hold

15 transistor TSH, a charge storage capacitor Ct connected
between the other end of the coupling capacitor Cc and
the ground node, and a potential clamp transistor TCLP
whose one end is connected to the connection node of
these two capacitors Cc, Ct and whose the other end is

20 supplied with bias voltage VVC, and one end of the
horizontal selection transistor TH is connected to the
connection node of two capacitors Cc, Ct.

Also, arranged in a third external region (not
shown) of the image region A are a vertical shift

25 register 2 for selecting and controlling a plurality of
vertical selection line 6 of the imaging region, a
pulse selector 2a for driving the readout line 4 or the

like of each row of the imaging region by selecting and
controlling the output pulse of the vertical shift
register 2, and a horizontal shift register 3 for
driving the horizontal selection transistor TH.

5   Further, arranged in a fourth external region (not
shown) of the imaging region A are a timing generation
circuit 10 for generating various internal signals,
based on an external input pulse signal at a
predetermined timing, and supplying to the pulse

10   selector 2a, the horizontal shift register 3, the noise
canceller circuit or the like, and a bias generation
circuit 11 for generating a predetermined bias
potential at one end or other of the potential clamp
transistor TCLP of the noise canceller circuit.

15   FIG. 10 is a timing waveform diagram showing an
example of the operation of the solid-state image
sensor shown in FIG. 9. Now, referring to FIG. 10, the
operation of the solid-state image sensor shown in
FIG. 9 will be described.

20   Signal charges generated by photoelectric
conversion of incident light are stored in the
photodiode PD.

In the horizontal blanking period, when the signal
charges of the photodiode PD are read out from the unit

25   cell 1 of any one row, first, each vertical signal line
VLIN is selected. Next, the signal line (ϕADRESi) of
the vertical selection line 6 of the row to be selected

is selected, and a vertical selection pulse signal
ϕADRES is applied thereto, thereby turning on the line
selection transistors Ta of one row.

For the unit cell 1 of one row thus selected, a
source follower circuit, comprised of the amplifying
transistor Tb and the load transistor TL supplied with
power supply potential VDD (for instance 3.3V) through
the row selection transistor Ta, is operated.

Next, in the unit cell 1 of one row thus selected,
a reset pulse signal ϕRESET is applied by selecting
the signal line (ϕRESETi) of the reset line 7, and the
voltage of the gate of the amplifying transistor Tb
(signal detection node DN) is reset to the reference
voltage for a fixed period, thereby providing the
reference voltage to the vertical signal line VLIN.
However, the gate potential of the amplifying
transistor Tb of the unit cell 1 of one row reset here
is changed, and the reset potential of the vertical
signal line VLIN of its other end with become uneven.

Therefore, to compensate the unevenness of the
reset potential of the vertical signal line VLIN, the
driving signal (ϕSH pulse) of the sample hold
transistor TSH in the noise canceller circuit is
previously turned on. Moreover, the connection node of
capacitors Cc, Ct of the noise canceller circuit is set
to the reference voltage, by turning on for a
predetermined time the driving signal (ϕCLP pulse) of

the potential clamp transistor TCLP after the reference voltage is output to the vertical signal line VLIN.

Next, the readout transistor Td is turned on by turning on the signal line (ϕREADi) thereof by selecting the readout line 4 of a predetermined row synchronizing with the readout pulse signal ϕREAD, after turning off the signal line (ϕRESETi) of the reset line 7, and the gate potential is changed by reading out the stored charges of the photodiode PD to the gate of the amplifying transistor Tb. The amplifying transistor Tb provides a voltage signal corresponding to the change amount of the gate potential to the corresponding vertical signal line VLIN and noise canceller circuit.

Thereafter, by turning off ϕSH pulse in the noise canceller circuit, a signal component corresponding to the difference between the read reference voltage and the signal voltage, in other words, the signal voltage without noise is stored in the capacitor Ct for the charge storage capacitor until the corresponding horizontal selection transistor TH is turned on.

Then, by turning off the signal line (ϕADRESi) of the vertical selection line 6 and controlling the vertical selection transistor Ta to off state to set the unit cell to non-selected state, the imaging region and each noise canceller circuit are disconnected electrically.

During the following effective horizontal period, after the reset by the horizontal reset signal HRS from the timing generation circuit 10, the horizontal shift register 3 performs the shift operation in

5   synchronization with the horizontal timing signal HCK. This allows to turn on sequentially the driving signal (ϕ H pulse) of the horizontal selection transistor TH and turn on the horizontal selection transistor TH sequentially.

10   In this way, the signal voltage of the connection node (signal conservation node) of the capacitors Cc, Ct in the noise canceller circuit is read out sequentially on the horizontal signal line HLIN, amplified and output by the output amplification

15   circuit AMP. Here, the aforementioned noise elimination operation is performed for each readout operation by one horizontal line.

FIG. 11 is a timing waveform diagram showing an example of operation of the timing generation circuit

20   10 and the vertical shift register 2 in FIG. 10. Here, a case where the CMOS image sensor of FIG. 9 is used by VGA (Video Graphic Array) system of one field (frame) = 1/30 Hz is shown.

Pulse signal ϕHP of 15.7 KHZ and clock signal ϕCK

25   of 24 MHz input from outside are shaped by a buffer circuit (not shown) and are input to the timing generation circuit 10. Pulse signal ϕVR of 30 KHZ and

pulse signal ϕHP of 15.7 KHZ input from outside are shaped by a buffer circuit (not shown) and are input to the vertical shift register 2.

5   The vertical shift register 2 clears completely the register output during "L" level period of the input pulse signal ϕVR and sets to "L" level, then performs the shift operation by the pulse signal ϕHP to set the output pulse signal ROi (i = ···, n, n+1, ···) to "H" level sequentially and the output pulse signal

10   ROi is applied to the pulse selector 2a.

The pulse selector 2a selects the signal line (ϕADRESi) of the vertical selection line 6, the signal line (ϕRESETi) of the reset line 7 and the signal line (ϕREADi) of the readout line 4 for each selected row,

15   and scans the selected row.

As mentioned above, the CMOS image sensor of FIG. 9 provides only once the respective output pulse signal ROi of the vertical shift register 2 for selecting and controlling a specific selected row

20   within one field period. Namely, as the photodiode PD discharges the stored charges only one by one field, it is impossible to perform an electronic shutter operation for controlling the exposure time by controlling the signal storage time in the photodiode

25   PD.

However, in general, solid-state imaging devices such as COMS image sensor are often used under various

external light such as, indoor or in open air, or
further, daytime or night time. Therefore, the
electronic shutter operation for adjusting the exposure
time and, consequently, setting the sensitivity to the
5   optimal value by controlling the charge storage period
in the photodiode according to the variation of
external light or the like, is often required.

Therefore, in addition to the vertical shift
register 2 for providing the output pulse signal ROi,
10 if a vertical shift register for the electronic shutter
for selecting and controlling each pixel row prior to
the vertical shift register 2 is provided to the
aforementioned CMOS image sensor of FIG. 9, the
photodiode signal storage time of each pixel row can be
15 controlled based on respective output pulse signals
from these two vertical shift registers, allowing, as a
result, to perform the electronic shutter operation.

Now, a configuration of an amplification type CMOS
image sensor capable of electronic shutter operation
20 will be shown schematically in FIG. 12 and, the
operation waveform of the vertical shift register in
FIG. 12 will be shown in FIG. 13.

In FIG. 12, the pulse signal ϕES of 30 KHZ and
the pulse signal ϕHP of 15.7 KHZ input from outside
25 are shaped respectively by a buffer circuit (not shown)
and applied to the vertical shift register 20 for the
electronic shutter at both the field period and the

horizontal period. This vertical shift register 20 for
the electronic shutter clears completely the register
output during "L" level period of the input pulse
signal ϕES and sets to "L" level, then performs the
5 shift operation by the pulse signal ϕHP to set the
output pulse signal ESi (i = ⋯, n, n+1, ⋯) to "H"
level sequentially and input to the pulse selector 2a.

The pulse selector 2a scans the pixel row of the
signal line ($\phi RESETi$) of the imaging region so as to
10 select the reset line 7 and the signal line ($\phi READi$)
of the readout line 4 for the pixel row where the
output pulse signals ROi, ESi from two vertical shift
registers 2, 20 are of "H" level. In this case, for
the signal line ($\phi ADRESi$) of the vertical selection
15 line 6, only the row to be selected where the output
pulse signal ROi from the readout vertical shift
register 2 is "H" level is selected and scanned.

Thus, as shown in FIG. 13, the signal line
($\phi READi$) of the readout line 4 in each pixel row is
20 turned on twice within one field period by two vertical
shift registers 2, 20. Namely, as the signal storage
timing and the signal readout timing can be set in
correspondence respectively to the output pulse signals
ROi, ESi from the vertical shift register 20 for the
25 electronic shutter and the readout vertical shift
register 2, consequently, the electronic shutter
operation for controlling the charge storage time in

the photodiode can be obtained.

As mentioned above, in the CMOS image sensor shown in FIG. 12, a readout driving signal is output from the pulse selector 2a to the readout line 4 in synchronization with the readout pulse signal ϕREAD supplied from the timing generation circuit 10, for either of signal storage timing or signal readout timing. This allows to perform the electronic shutter operation for controlling the charge storage time in the photodiode by 1H unit.

On the other hand, it is highly expected that the CMOS image sensor be used in an environment where incident light amount is extremely abundant such as daytime outdoor, and it is required to obtain always a good image without risk of clipping of the high brightness side even under such environment. For this sake, it is desirable to realize a rapid electronic shutter operation reducing the charge storage time of the photodiode to less than 1H.

Considering such situation, the Applicant has proposed a solid-state imaging device (Japan Patent Application No. 11-286469) capable of controlling the minimum charge storage time of the photodiode to less than 1H and performing an extremely high speed electronic shutter operation.

By the way, the aforementioned CMOS image sensor shown in FIG. 9 or FIG. 12 has a problem of low dynamic

range that a person by the window photographed from indoor is imaged dark, and when the sensitivity is focused to the person, the scenery of the window will become white and can not be reproduced. Moreover, as

5 the dynamic range is determined by the signal charge amount stored in an unit cell, the capacity of the signal storage portion will be lowered to reduce the saturated signal amount and the dynamic range when the pixel cell size is reduced or the driving voltage is

10 lowered. This low dynamic range will prevent from imaging from the small signal to large signal area.

The Applicant has already proposed a technique for resolving the problem of such low dynamic range (Japan Patent Application No. 10-185121). The technique

15 according to the proposal is that a part of the amount of charges, read out at the signal detection node produced by the photodiode for a certain period, is removed to limit the charges at the signal detection node and that charges produced by the photodiode after

20 this period are read out to add them to the charges stored at the signal detection node. However, it is desired that a system for increasing the dynamic range suitable for the readout driving control in the amplification type CMOS image sensor.

25   BRIEF SUMMARY OF THE INVENTION

The present invention has been made to eliminate the above problems, and it is an object of the present

invention to provide a solid-state imaging device
capable of increasing remarkably the dynamic range of
amplification type CMOS image sensor, and obtaining a
good image over small signal to large signal without
5   being clipped.

It is another object of the present invention to
provide a solid-state imaging device capable of
increasing remarkably the dynamic range while carrying
out the electronic shutter operation in the amplifica-
10   tion type CMOS image sensor, and obtaining a good image
from small signal to large signal without being clipped.

According to one aspect of the present invention,
there is provided a solid-state imaging device which
comprises an imaging region including unit cells
15   arranged in a matrix of rows and columns to provide a
plurality of pixel rows, each of the unit cells having
photoelectric conversion means for photoelectrically
converting incident light, applied to pixels to store
signal charges, readout means for reading out stored
20   signal charges at a detection node, and amplifying
means for amplifying read signals; and a readout
voltage switching circuit for setting readout driving
signals, applied to the readout means, to any one of
a plurality of voltages different from one another
25   according to internal control.

According to another aspect of the present
invention, there is provided a second solid-state

imaging device which comprises an imaging region including unit cells arranged in a matrix of rows and columns to provide a plurality of pixel rows, each of the unit cells having photoelectric conversion means

5 for photoelectrically converting incident light, applied to pixels to store signal charges, readout means for reading out stored signal charges at a detection node, and amplifying means for amplifying read signals; a plurality of readout lines provided in

10 a horizontal direction corresponding to each pixel row in the imaging region, the plurality of read lines transmitting readout driving signals for driving respective readout means of the unit cell in respective corresponding pixel row; a pulse production circuit for

15 producing a plurality of pulses for respective pixel rows as pulse signals for controlling readout timing in the plurality of pixel rows; a readout voltage switching circuit for setting a readout driving signal voltage, applied to the readout means corresponding to

20 a part of a plurality of pulses, to a voltage different from the readout driving signal voltage applied to the readout means according to the other pulse of the plurality of pulses; and a plurality of vertical signal lines, disposed in correspondence to respective pixel

25 column in the imaging region, for transmitting in the vertical direction signals output respectively from the unit cell of each pixel row.

Additional objects and advantages of the invention
will be set forth in the description which follows, and
in part will be obvious from the description, or may be
learned by practice of the invention. The objects and
5   advantages of the invention may be realized and
obtained by means of the instrumentalities and
combinations particularly pointed out hereinafter.

BRIEF DESCRIPTION OF THE SEVERAL VIEWS OF THE DRAWING

The accompanying drawings, which are incorporated
10   in and constitute a part of the specification,
illustrate presently preferred embodiments of the
invention, and together with the general description
given above and the detailed description of the
preferred embodiments given below, serve to explain the
15   principles of the invention.

FIG. 1 is a block diagram showing schematically an
amplification type CMOS image sensor according to a
first embodiment of the present invention;

FIG. 2 is a circuit showing an example of pulse
20   selector in FIG. 1;

FIG. 3 is a timing waveform diagram for
illustrating electronic shutter operation, dynamic
range control operation, and readout operation in the
CMOS image sensor of FIG. 1;

25   FIG. 4 is a waveform diagram showing external
input pulse signals ϕES, ϕDR, ϕVR, ϕHP and
respective output pulse signals ROi, ESi, DRi of the

vertical shift registers of the CMOS image sensor of FIG. 1;

FIG. 5 is a waveform diagram showing signals remarking the operation of n th horizontal line in an imaging region of the CMOS image sensor of FIG. 1;

FIG. 6 shows schematically a cross sectional structure and an electric potential variation for illustrating a photodiode operation from time t0 to t3 shown in FIG. 5;

FIG. 7 is a characteristic showing an example of photoelectric conversion characteristic of the CMOS image sensor of FIG. 1;

FIG. 8 is a block diagram showing schematically an amplification type CMOS image sensor according to a second embodiment of the present invention;

FIG. 9 is a block diagram showing schematically a conventional amplification type CMOS image sensor;

FIG. 10 is a timing waveform diagram showing an example of the operation of the solid-state image sensor shown in FIG. 9;

FIG. 11 is a timing waveform diagram showing an example of the operation of the timing generation circuit and a vertical shift register in FIG. 10;

FIG. 12 is a block diagram showing schematically a configuration of an amplification type CMOS image sensor capable of electronic shutter operation; and

FIG. 13 is a timing waveform diagram for showing

the operation of the vertical shift register in FIG. 12.

DETAILED DESCRIPTION OF THE INVENTION

Embodiments of the present invention will be described in detail with reference to the drawing.

5   FIG. 1 is a block diagram showing schematically an amplification type CMOS image sensor according to a first embodiment of the present invention.

Compared to the CMOS image sensor shown in FIG. 12, the CMOS image sensor of FIG. 1 is mostly similar to

10   except the following points, and those same as in FIG. 12 have the same reference numerals.

(1) A vertical shift register 30 is provided for generating sequentially pulses DRi (i = $\cdots$, n, n+1, $\cdots$) of a dynamic range control, based on the external input

15   pulse ϕDR.

Namely, the image sensor includes a pulse generation circuit B comprised of three vertical shift registers 2, 20, 30 for producing three pulses ESi, DRi, ROi for respective pixel rows, as a pulse signal source

20   for controlling the readout timing in the readout transistor Td.

(2) A voltage VDR of a readout driving signal is applied to the readout transistor Td corresponding to the pulse DRi of the dynamic range control. In order

25   to set the voltage VDR to a lower voltage than a voltage VDD of the readout driving signal applied to the readout transistor Td in correspondence to the

pulse ESi for the electronic shutter and the pulse ROi

for usual readout, a VREAD generation circuit 31 is

provided.

Namely, a readout voltage switching circuit C is

provided, which has the function to control the readout

driving signal voltage (readout voltage VREAD) applied

to the readout transistor Td to either voltage of a

plurality of voltage values VDD, VDR.

Here, a concrete example of the VREAD generation

circuit 31 which is the readout voltage switching

circuit C will be described. A voltage VDD is applied

to one end of the voltage dividing circuit where

resistors R1, R2 are connected in series, and an output

node is connected to this one end through a switch S1.

The series connection node of the resistors R1, R2 is

connected to the output node through a switch S2, and

the other end of the voltage dividing circuit is

connected to the ground node through a switch S3. The

switches S2, S3 are controlled by the control signal

φVP, and the switch S1 is controlled by a signal

obtained by inverting the switching control signal φVP

with an inverter circuit IV.

Thereby, when S1 is controlled to ON state among

switches S1, S2, S3 and S2 and S3 are OFF state, VDD is

output to the output node as VREAD, and when S2 and S3

are controlled to ON state and S1 to OFF state, VDD is

divided and VDR is output to the output node as VREAD.

(3) The pulse selector circuit 2b is operated as vertical driving means for selecting the output signals ROi, ESi, DRi of three vertical shift registers 2, 20, 30 and providing the readout driving signal set to the readout voltage VREAD (VDD or VDR) supplied from the VREAD generation circuit 31.

(4) The timing generation circuit 10 is provided to have a function to supply the VREAD generation circuit 31 with the switching control signal ϕVP and the pulse selector circuit 2b with a pulse signal ϕDRREAD of the dynamic range control.

Namely, in FIG. 1, the imaging region A includes units cells 1 of one pixel/one unit arranged in a matrix of rows and columns. Each unit cell 1 is comprised of, for example, four transistors Ta, Tb, Tc, Td and one photodiode PD. Namely, each unit cell 1 comprises a photodiode PD that the ground potential is applied to the anode, a readout transistor (shutter gate transistor) Td whose one end is connected to the cathode of the photodiode PD, an amplifying transistor Tb whose gate is connected to the other end of the readout transistor Td, a vertical selection transistor (row selection transistor) Ta whose one end is connected to one end of the amplifying transistor Td, and a reset transistor Tc whose one end is connected to the gate of the amplifying transistor Tb.

In addition, the imaging region A comprises a

readout line 4 connected in common to the gate of each

readout transistor Td of the unit cells 1 in the same

row, a vertical selection line 6 connected in common to

the gate of each vertical selection transistor Ta of

5   the unit cells 1 in the same row, and a reset line 7

connected in common to the gate of each reset

transistor Tc of the unit cells 1 in the same row, in

correspondence to each pixel row.

Moreover, the imaging region A includes a vertical

10   signal line VLIN connected in common to the other end

of each amplifying transistor Tb of the unit cells 1 in

the same row, and a power supply line 9 connected in

common to the other end of each reset transistor Tc and

to the other end of each vertical selection transistor

15   Ta of the unit cells 1 in the same row, in corre-

spondence to each pixel column.

Further, arranged in the horizontal direction in

the first external region (not shown) are a plurality

of load transistors TL connected respectively between

20   one end of the vertical signal line VLIN and the ground

node and supplied with bias voltage VVL at the gate.

Moreover, a plurality of noise canceller circuits

comprised of, for instance, two transistors TSH, TCLP

and two capacitors Cc, Ct are arranged in the

25   horizontal direction in the second external region (not

shown) of the imaging region A. And, a plurality of

horizontal selection transistors TH connected to

respective other ends of the vertical signal line VLIN
through each noise canceller circuit are arranged in
the horizontal direction.

Further, a horizontal signal line HLIN is

5   connected in common to each other end of the horizontal
selection transistors TH, and a horizontal reset
transistor (not shown) and an output amplifying circuit
AMP are connected to the horizontal signal line HLIN.

Here, each noise canceller circuit includes a

10 sample hold transistor TSH whose one end is connected
to the other end of the vertical signal line VLIN, a
coupling capacitor Cc whose one end is connected to the
other end of the sample hold transistor TSH, a charge
storage capacitor Ct connected between the other end of

15 the coupling capacitor Cc and the ground node, and a
potential clamp transistor TCLP whose one end is
connected to the connection node of these two
capacitors Cc, Ct and whose other end is supplied with
bias voltage VVC, and one end of the horizontal

20 selection transistor TH is connected to the connection
node of the two capacitors Cc, Ct.

Also, arranged in the third external region (not
shown) of the imaging region A are the readout vertical
shift register 2 for selecting and controlling a

25 plurality of vertical selection lines 6 of the imaging
region, the vertical shift register 20 for the
electronic shutter, the vertical shift register 30 for

the dynamic range control, the pulse selector 2b for driving the readout line 4 or the like of each row of the imaging region by selecting and controlling the output pulses of the three vertical shift registers 2, 20, 30, and the horizontal shift register 3 for driving a plurality of horizontal selection transistors TH.

Further, arranged in the fourth external region (not shown) of the imaging region A are the timing generation circuit 10a for generating various internal control signals (ϕROREAD, ϕESREAD, ϕDSREAD, ϕRESET, ϕADRES to be supplied to pulse selector 2b; ϕSH, ϕCLP to be supplied to the noise canceller circuit; ϕVP to be supplied to the VREAD generation circuit 31; pulse signals, HRS, HCK to be supplied to the horizontal shift register 3 or other pulse signals) at a predetermined timing, based on the external input pulse signals ϕHP, ϕCK, thereby supplying the pulse selector 2b, the horizontal shift register 3, the noise canceller circuit, VREAD generation circuit 31 or the like therewith, and the bias generation circuit 11 for generating a predetermined bias potential at one end or other of the potential clamp transistor TCLP of the noise canceller circuit.

The vertical shift register 20 for the electronic shutter clears completely the register outputs during "L" level period of ϕES and sets to "L" level when the external input pulse signals ϕES, ϕVR are shaped

respectively by a buffer circuit (not shown) and input
at the field and horizontal periods. The shift
register carries out then the shift operation by the
pulse signal ϕHP to set the output pulse signal ESi

5 (i = ⋯, n, n+1, ⋯) to "H" level sequentially and
provides to the pulse selector 2b. In this example,
the pulse signal ESi for the electronic shutter is
produced during the horizontal blanking period.

     The vertical shift register 30 for dynamic range

10 control clears completely the register outputs during
"L" level period of ϕDR and sets to "L" level when the
external input pulse signals ϕDR, ϕHP are shaped
respectively by the buffer circuit (not shown) and
input at field and horizontal periods, then carries out

15 the shift operation by the pulse signal ϕHP to set the
output pulse signal DRi (i = ⋯, n, n+1, ⋯) to "H"
level sequentially and input to the pulse selector 2b.
In this example, the pulse signal DRi for the dynamic
range control is produced during the horizontal

20 blanking period.

     The vertical shift register 2 for readout clears
completely the register outputs during "L" level period
of ϕVR and sets to "L" level when the external input
pulse signals ϕVR, ϕHP are shaped respectively by the

25 buffer circuit (not shown) and input at field and
horizontal periods, then performs the shift operation
by the pulse signal ϕHP to set the output pulse signal

ROi (i = ⋯, n, n+1, ⋯) to "H" level sequentially and
input to the pulse selector 2b. In this example, the
pulse signal ROi for readout is produced during the
horizontal blanking period.

5   Then, the VREAD generation circuit 31 receiving
ϕVP pulse from the timing generation circuit 10a
changes over the readout voltage VREAD to VDD or VDR
and supplies the pulse selector 2b therewith. In this
case, VREAD is set to VDD during "L" period of ϕVP and
10   VREAD is set to VDR lower than VDD during "H" period of
ϕVP.

     FIG. 2 is a circuit showing an example of pulse
selector 2b in FIG. 1.

     As shown in FIG. 2, input to the pulse selector 2b
15   are the output signal ESi (ESn in this example) of the
vertical shift register 20 for the electronic shutter,
the output pulse signal DRi (DRn in this example) of
the vertical shift register 30 for the dynamic range
control and the output pulse signal ROi (ROn in this
20   example) of the readout vertical shift register 2, and
further input to the pulse selector 2b are the timing
signals ϕADRES, ϕRESET, ϕESREAD, ϕDRREAD, ϕROREAD
supplied from the timing generation circuit 10a. The
logic processing of these input signals is carried out
25   to provide (supply to the imaging region) the vertical
selection line driving signal ϕADRESi (i = ⋯, n,
n+1, ⋯), the reset signal ϕRESETi (i = ⋯, n, n+1, ⋯)

and readout driving signal ϕREADi (i = $\cdots$, n, n+1, $\cdots$),
thereby constituting a logic gate.

Namely, when the output signal ESi of the vertical
shift register 20 for the electronic shutter is in ON
state, the timing signal ϕESREAD is selected to
provide the driving signal ϕESREADi, when the output
signal DRi of the vertical shift register 30 for the
dynamic range control is in ON state, the timing signal
ϕDRREAD is selected to provide the driving signal
ϕDRREADi, and when the output signal ROi of the
vertical shift register 2 for the readout is in ON
state, the timing signal ϕROREAD is selected to
provide the driving signal ϕROREADi respectively.
VREAD controls the voltage amplitude of these readout
driving signals ϕREADi and the voltages of ϕESREADi
and ϕROREADi are VDD and the voltage of ϕDRREADi is
VDR.

When any one of the output signal ESi of the
vertical shift register 20 for the electronic shutter,
the output signal DRi of the vertical shift register 30
for the dynamic range control or the output signal ROi
of the vertical shift register 2 for readout is in ON
state, the timing signal ϕRESET is selected and output
as the reset signal ϕRESETi.

When the output signal ROi of the vertical shift
register 2 for readout is in ON state, the timing
signal ϕADRES is selected and output as the vertical

selection line driving signal ϕADRESi.

An operation of the CMOS image sensor of FIG. 1 will be described.

The basic operation of the CMOS image sensor of FIG. 1 is same as the operation of the CMOS image sensor described referring to FIG. 9, so the outline thereof will be described here.

First, ϕADRESi is turned ON to operate the source follower circuit. Next, ϕRESETi is turned ON to reset the signal detection node DN. Thereafter, the potential of the signal detection node DN is output as a reference voltage. At this time, ϕSH and ϕCLP are turned ON and the reference voltage is set by the noise canceller circuit.

Next, the signal charges stored by the photoelectric conversion through the photodiode PD are read out by turning ON ϕREADi, and output to the noise canceller circuit through the amplifier transistor Tb and the source follower circuit. The signal voltage output to the noise canceller circuit can be stored in the capacitor Ct during the effective period, by turning OFF ϕSH. Signal voltage stored in the capacitor Ct is output to the horizontal signal line HLIN by sequentially applying ϕHi to the horizontal selection transistor TH during the effective period.

Now, the characterizing portion of the operation of the CMOS image sensor in FIG. 1 will be described in

detail.

FIG. 3 is a timing waveform diagram showing the operation example of the timing generation circuit 10a, three vertical shift register 2, 20, 30 and the pulse

5   selector 2b in FIG. 1 for explaining the electronic shutter operation, the dynamic range control (increase) operation, and the readout operation in the CMOS image sensor of FIG. 1. Here, a case where the CMOS image sensor of FIG. 1 is used by VGA (Video Graphic Array)

10   system of one field (frame) = 1/30 Hz is shown.

Upon the reception of ϕHP pulse, the timing generation circuit 10a provides pulses ϕADRES, ϕRESET, ϕESREAD, ϕDRREAD, ϕROREAD, ϕSH, ϕCLP, ϕVP, and also pulses HRS, HCK or the like during the horizontal

15   blanking period.

Upon the reception of HRS pulse and HCK pulse from the timing generation circuit 10a, the horizontal shift register 3 provides sequentially ϕHi (i = $\cdots$, n, n+1, $\cdots$) during the effective horizontal period.

20   The vertical shift register 20 for the electronic shutter is reset by ϕES as a trigger prior to the vertical shift register 30 for the dynamic range control and the readout vertical shift registers 2, and thereafter, provides ESi sequentially in

25   synchronization with ϕHP. Corresponding to this ESi, the driving signal ϕESREADi is output to the readout line 4 from the pulse selector 2b to carry out the

selection operation of the pixel row.

Thereafter, the vertical shift register 30 for the dynamic range control is reset by ϕDR as a trigger, and then provides DRi sequentially in synchronization

5 with ϕHP. Corresponding to this DRi, the pulse selector 2b provides the driving signal ϕDRREADi to the readout line 4 to perform the selection operation of the pixel row.

Thereafter, the vertical shift register 2 is

10 reset by ϕVR as a trigger, and then provides ROi sequentially in synchronization with ϕHP. Corresponding to the ROi, the pulse selector 2b provides the driving signal ϕROREADi to the readout line 4 to perform the selection operation of the pixel

15 row.

FIG. 4 is a waveform diagram showing external input pulse signals ϕES, ϕDR, ϕVR, ϕHP and respective output pulse signals ROi, ESi, DRi of the vertical shift registers 2, 20, 30 of the CMOS image

20 sensor in FIG. 1.

After being reset by corresponding input pulse signals ϕVR, ϕES, ϕDR, the vertical shift register 2, 20, 30 carry out the shift operation in synchronization with ϕHP to generate output pulses ROi, ESi, DRi.

25 FIG. 5 is waveforms showing signals paid attention to the operation of n-th horizontal line in the imaging region of the CMOS image sensor in FIG. 1. Here, HLBK

is a pseudo pulse signal for dividing one horizontal period into horizontal blanking period and effective horizontal period.

First, at the time t0, the photodiode of the n-th line converts optical signals into charges and stores the same. Next, by the time t1, the output pulse ESn of the vertical shift register 20 for the electronic shutter becomes "H" thereby to provide ϕRESETn and ϕREADn (voltage VDD at this time) from the pulse selector 2b. After this first shot ϕRESETn resets the signal detection node DN, all stored charges in the photodiode are read out by the first shot ϕREADn. From the following time t1, the photodiode stores signal charges again.

Next, the output pulse DRn of the vertical shift register 30 for the dynamic range control becomes "H" to provide ϕRESETn and ϕREADn (voltage being VDR at this time) from the pulse selector 2b. After the second shot ϕRESETn resets the signal detection node DN, only large signal charges equal or more than the predetermined value of charges stored in the photodiode are read out by ϕREADn. At this time, if no signal charges equal or more than the predetermined value are stored in the photodiode, signal charges are not read out. This operation is realized by setting the amplitude of voltage VDR of the second shot readout driving signal READn to be lower than the VDD. This

operation is confirmed by the experimentation within
the VDR range from 1 V to less than 3.3V, when VDD is
3.3V. From the following time t2 the photodiode stores
signal charges again.

5   Next, the output pulse ROn of the vertical shift
register 2 for to signal readout becomes "H" thereby
providing ϕADRESn, ϕRESETn and ϕREADn (voltage VDD at
this time) from the pulse selector 2b. After the third
shot ϕRESETn resets the signal detection node DN, all
10   stored charges in the photodiode are read out by the
third shot ϕREADn. The read out stored charges are
read out as a signal to the vertical signal line VLIN
by ϕADRESn.

When ESn, DRn, ROn are not set to "H" at the same
15   time during the same horizontal blanking period, a
single shot of ϕRESET will operate in place of three
shots, and only a single reset pulse signal ϕRESET in
FIG. 3 may be output. Otherwise, the timing signal
ϕESREAD from the timing generation circuit 10a can
20   also be made common, and the driving signal ϕREADn
during the electronic shutter operation and the driving
signal ϕREADn during signal readout can be set to the
same phase.

FIG. 6 shows schematically the cross sectional
25   structure of photodiode PD, the signal detection node
DN and the signal detection transistor Td provided on a
semiconductor substrate and the electric potential

variation for explaining the photodiode operation from
time t0 to t3 shown in FIG. 5.

    The signal detection node DN including the
photodiode PD and n type region is formed on a silicone
substrate of p well or p substrate. The signal readout
transistor Td has a channel region between n type
region of the photodiode PD and the signal detection
node DN, and has, for example, a polysilicon gate
electrode (readout gate electrode) formed thereon
through a gate insulating film.

    At time t0, the photodiode PD converts optical
signals into charges and stores them. At the readout
operation of the electronic shutter of time t1, a
portion under the readout gate electrode becomes an
electric potential PVDD, and all charges stored in the
photodiode PD are read out into the signal detection
node DN having a well of deeper potential. Then, the
signal charges are stored by the photodiode PD again.

    At the readout operation of the dynamic range
control (increase) of time t2, a portion under the
readout gate electrode becomes an electric potential
PVDR. At this time, if large signal charges
overflowing from the electric potential PVDR is stored
in the charges of the photodiode PD, the signal charges
overflowing from the electric potential PVDR is read
out from the photodiode PD. On the contrary, if only
the small signal charges less than the electric

potential PVDR is stored in the photodiode PD, the
signal charges less than the electric potential PVDR is
not read out.

At the time t3 just before the readout operation,
the photodiode PD stores the signal charges again, and
this stored charges are the sum of ESR signal charges
stored after the aforementioned electronic shutter
operation and WDR signal charges stored after the
dynamic range control operation.

FIG. 7 shows the characteristic of PD signal
change amount with respect to the optical input signal,
as an example of the photoelectric conversion
characteristic of the CMOS image sensor of FIG. 1.

For the optical input signal in a small area
generating signal charges up to a fixed value (KNEE
point), the amount of signal charges of PD is stored
with ESR signal charges given by the storage time TS-TD
in FIG. 5. Therefore, the gradient of the photo-
electric conversion becomes large as shown by the solid
line. For the optical input signal in a large area
generating signal charges larger than KNEE point, as
its signal charge amount is stored with WDR signal
charge given by the storage time TD in FIG. 5, the
gradient of the photoelectric conversion becomes small
as shown by the solid line, allowing a wide dynamic
(DR) operation. The gradient of the photoelectric
conversion due to the storage of the ESR signal charges

is determined by the storage time TS in the electronic
shutter operation.

Besides, the gradient of the photoelectric
conversion due to the storage of WDR signal charges can
be controlled by the storage time TD of the dynamic
range control operation.

As apparent from FIGS. 5 and 7, the gradient of
photoelectric conversion in the ESR signal charges is
large as its storage time is long, while the gradient
of the photoelectric conversion in the WDR signal
charges is small as its storage time is short. In
other words, when the charges of the small signal are
stored, its gradient of the photoelectric conversion is
large as only ESR signal charges having the long
storage time is stored. On the contrary, when the
charges of the large signal are stored, the gradient of
the photoelectric conversion becomes small for a value
equal or more than a desired value (WDR signal charge),
allowing, as a result, to increase the dynamic range.

Here, KNEE point corresponds to the electric
potential PVDR in FIG. 6, which can be controlled by
the difference between the voltages VDD and VDR of the
readout driving signal φREADn. For example, it
becomes possible to increase further the dynamic range
by 10 times, by reducing the storage time TS in the
electronic shutter operation to 1/10.

In the CMOS image sensor shown in FIG. 1, the

external input pulse signals are effectively used by
the timing generation circuit 10a to produce various
signals. Therefore, the electronic shutter operation
with a remarkably high speed can be realized at low
cost without increasing the circuit scale in, for
example, the pulse selector 2b and the like.

As the readout driving signal voltage for the
dynamic range control, one single voltage value VDR is
employed in the embodiment. However, the voltage value
may be selected from a plurality of voltage values VDR1,
VDR2, ··· to modify the dynamic range characteristics.

Now, the mechanism of dynamic range increase will
be described referring to the aforementioned FIGS. 4
to 7.

When the output of respective registers RO, DR,
ES is "H" in FIG. 4, φREADN pulses of FIG. 5 are
generated. In other words, when the register ES is "H",
VDD1 of φREADN is generated, when the register DR is
"H", VDR2 is generated, and when the register RO is "H",
VDD3 is generated. According to such voltages, the
signal charges stored in the photodiode PD is readout
at the detection node DN. During the signal storage
operation in the standard 30 Hz period, there is no
output from the registers ES and DR, and only the
register RO is output. Signals are stored in the
signal storage operation of n-th line during 30 Hz
period where it become "H". At n+1 th line, signals

are stored during 30 Hz period with a delay of only one
horizontal period (1H). As the operation of FIG. 6,
the signal charges stored in the photodiode PD are read
out to the detection node DN by ϕREAD pulse applied to
5   READ gate.

On the other hand, the automatic sensitivity
adjustment is carried out by the electronic shutter
operation, and in the automatic sensitivity adjustment,
the registers ES and RO of FIG. 4 become "H". For
10   instance, the storage time in the photodiode PD is the
time from "H" (time t1) of ESn to "H"(time t4) of ROn
at n-th line. This storage time is shorter than 30 Hz.
Similarly, the storage time at n+1 th line is delayed
by one horizontal period (1H) and shorter than the
15   period of 30 Hz. The storage time of t1 to t4 is
constituted so as to be automatically varied according
to signal amount of the object. This storage time is
indicated as the time from VDD1 to VDD3 of ϕREADn in
FIG. 5. In the electronic shutter operation, VDR2 is
20   not generated, and VDD1 and VDD2 are of the same
voltage.

As obvious from the foregoing explanation, the
solid-state imaging device of the present invention
includes a wide dynamic range operation in addition to
25   the automatic sensitivity adjustment by the electronic
shutter operation.

In other words, in order to carry out the wide

dynamic range operation, the readout voltage switching

circuit C and the register DR as shown in FIG. 1 and

FIG. 4 are provided. When the register DR of FIG. 4 is

"H", VDR2 which is ϕREAD pulse of FIG. 5 is generated.

5   The voltage of this VDR2 is set lower than the voltage

of VDD1. Further, as shown in FIG. 4, two kings of

signal storage times of the photodiode PD are provided,

and they are added to each other and read out. That is,

the first storage time is a time from "H" (time t1) of

10   the register ES to "H" (time t4) of RO, and the second

storage time is a time from "H" (time t2) of the

register DR to "H" (time t4) of RO. In the photodiode

PD, these first and second storage times are added and

read out to increase the dynamic range. In FIG. 5, the

15   first storage time is shown as TS and the second

storage time as TD.

The addition of storage times TS and TD in the

photodiode PD will be described using FIG. 6. In

FIGS. 5 and 6, the time before VDD1 of ϕREADn pulse is

20   set to t0, time of VDD1 as t1, time of VDR2 as t2, time

before VDD3 as t3 and time of VDD3 as t4, respectively.

As mentioned above, FIG. 6 shows the cross

sectional structure of the photodiode PD having one

pixel and the potential diagram, and the potential

25   diagram shows the large signal storage operation of

large optical signal amount and the low signal storage

operation of small optical signal amount.

At time t0, the optical signals entered the photodiode PD are converted into charges and stored. At time t1, voltage of VDD is applied to READ gate and all signal charges stored in the photodiode PD are read out into the signal detection node DN. Thereafter, the optical signals entered the photodiode PD by the time t4 is converted into charges and stored. This period corresponds to the storage time of the electronic shutter operation.

In the large signal amount storage operation, voltage of VDR is applied to READ gate at the time t2. The voltage VDR is set to a voltage lower than the voltage VDD. PVDD and PVDR are respectively electric potentials generated by application of voltage VDD and an electric potential generated by application of voltage VDR.

When the amount of optical signals is large, the signal charges are saturated in the photodiode PD by the time t2. When the voltage VDR is applied to READ gate at the time t2, the potential under READ gate becomes PVDR. Among the signal charges of the photodiode PD, signal charges larger than the potential PVDR are read out to the detection node DN. Then, READ gate is closed to store again the signal charges in the photodiode PD.

In the small signal amount storage operation, as the signal charges stored in the photodiode PD at the

time t2 are smaller than the potential PVDR, they are
not read out to the detection node DN, and the storage
operation is continued.

In the conventional storage operation of the large
signal amount, the signal charge amount Qsig stored in
the photodiode PD is substantially equal to the
saturated signal charge amount Qmax determined by both
the potential PVDD and the area of the photodiode PD
and, as shown by the dotted line in FIG. 7, it is
normally saturated at the saturated signal charge
amount Qmax.

As mentioned above, according to the present
invention the signal charge amount Qsig is obtained
given by:

Qsig = Q (PVDD - PVDR) + QWDR
Therefore, the dynamic range is increased by increasing
the signal charge amount of this QWDR. The signal
charge amount Q (PVDD - PVDR) is the signal charge
amount stored by he difference of PVDD potential, which
is the potential of the photodiode PD, and PVDR
potential, and the signal charge amount QWDR is stored
during the storage time TD of wide DR in FIG. 5.

FIG. 8 shows schematically a circuit structure of
an amplification type CMOS image sensor according to a
second embodiment of the present invention.

This CMOS image sensor includes an AD conversion
circuit 21 having a noise reduction function, and

converts analog signal transmitted to a plurality of vertical signal line VLIN into digital signals by the AD conversion circuit 21 to provide output signals.

Now, points different from the CMOS image sensor shown in FIG. 1 will be described mainly.

Namely, in the AD conversion circuit 21 of the CMOS image sensor shown in FIG. 8, a comparator CMP connected to one end of the vertical signal line VLIN for each pixel column is disposed in the horizontal direction. This comparator CMP compares analog signals from the vertical signal line VLIN with the reference signal VREF provided from the reference signal generation circuit 22. This reference signal VREF is, basically, a RAMP wave whose voltage increases with the lapse of time. The comparator CMP counts such a timing that the signal voltage, from which noise is removed, and the reference signal VREF are balanced, and converts analog signals into 10 bit digital signals by latching the counted value.

Besides, the comparator CMP includes a sample hold capacitor (not shown) in order to obtain the difference between the reference voltage and the signal voltage similarly to the noise canceller circuit in FIG. 1 and, the signal voltage with the removed noise is produced here.

Further, within the AD conversion circuit 21, a latch circuit LATCH and a switch circuit SW are

arranged in the horizontal direction so as to correspond to the comparator CMP for each pixel column respectively. The latch circuit LATCH holds 10 bit digital signals output from the comparator CMP, while the switch circuit SW reads out sequentially digital signals, held at each latch circuit LATCH, to the output signal lines DATA 0 to DATA 9 of the number corresponding to the number of bits by sequentially turning on by the driving signal (ϕHn pulse) supplied from the horizontal shift register 3.

A count signal ADCX and a horizontal synchronization signal HAD are input to the AD conversion circuit 21 and the reference signal generation circuit 22 from the timing generation circuit 10b, thereby controlling their operations.

External input pulse signals ϕVR, ϕES, ϕDR, ϕHP may be input directly to three vertical shift registers 2, 20, 30 as shown in the drawing. However, these external input pulse signals ϕVR, ϕES, ϕDR, ϕHP supplied at field period or horizontal period may be input to the timing generation circuit 10b to produce internal pulse signals therein, and the internal pulse signals may be applied to three vertical shift registers 2, 20, 30.

Moreover, as necessary, a command decoder circuit for receiving external command signals may be connected to the timing generation circuit 10b to adjust the gain,

the offset or the like of the timing generation circuit
10b or AD conversion circuit 21 by the output signals
from the command decoder circuit.

In the CMOS image sensor shown in FIG. 8, for
5   instance, the control signals output from the timing
generation circuit 10b to the pulse selector 2b can be
generated during the effective horizontal period of the
driving signals ϕREADi for the electronic shutter or
the dynamic range control by modifying the supply
10 timing thereof. Therefore, since increased are degrees
of freedom of changing the storage time TS of the
electronic shutter operation and the storage time TD of
the dynamic range control operation in FIG. 5, this may
be effective on controlling the wide dynamic range
15 operation. The reason is as follows.

Namely, when the electronic shutter pulse signal
ϕESREAD or dynamic range control pulse signal ϕDRREAD
is input to the pulse selector 2b during the effective
horizontal period, and the readout driving signal
20 ϕREADi for the electronic shutter or dynamic range
control is input to the imaging area during the
effective horizontal period, unwanted noise may enter
the analog signals due to variation or change of the
power supply voltage or ground voltage generated at
25 that time. In order to avoid such problems, the CMOS
image sensor of FIG. 8 can be provided so that the
operations of the AD conversion circuit 21 and the

reference signal generation circuit 22 are temporarily
stopped before and after the input of electronic
shutter pulse signal φESREAD or dynamic range control
pulse signal φDRREAD during the effective horizontal

5   period, based on the control by the count signal ADCK
from the timing generation circuit 10b.

For example, in the CMOS image sensor as shown in
FIG. 1, analog signals of one horizontal line are read
out sequentially into the horizontal signal line HLIN

10 during the effective horizontal period. In this case
when external pulse signals are supplied at this time,
unwanted noise may enter the analog signals depending
upon the variation of the power supply voltage or
ground voltage.

15 On the other hand, in the CMOS image sensor as
shown in FIG. 8, the digital signals of one horizontal
line are read out into the output signal lines DATA0 to
DATA9 during the effective horizontal period after
having converted the analog signals into the digital

20 signals. Therefore, unwanted entrance of noise due to
the variation of the power supply voltage or ground
voltage can almost be neglected for such digital
signals. As for analog signals before AD conversion,
it can be possible to avoid the entrance of unwanted

25 noise due to the variation of the power supply voltage
or ground voltage by stopping temporarily the operation
of AD conversion circuit 21 and the reference signal

generation circuit 22, as shown by the waveform of the
ramp wave RAMP in FIG. 8, before and after the input of
the electronic shutter pulse signal ϕESREAD or dynamic
range control pulse signal ϕDRREAD.

5 As for the CMOS image sensor without AD conversion
circuit 21 as shown in FIG. 1, it may be possible to
avoid the entrance of unwanted noise due to the
variation of the power supply voltage or ground voltage,
in the case where the electronic shutter pulse signal

10 ϕESREAD or dynamic range control pulse signal ϕDRREAD
are input during the effective horizontal period, by
providing a correction circuit for correcting the
influence of noise entering the analog signals, or by
mixing circuit blocks for electrically isolated power

15 supply, ground voltage system.

  Each unit cell used for the imaging region in
respective CMOS image sensors is not particularly
limited to one pixel/one unit including four
transistors and one photodiode PD. As unit cells, two

20 pixel/one unit including five transistors and two
photodiodes can also be employed. Further, stacked
photoelectric conversion means may be used in unit
cells. Moreover, various modifications are also
possible without departing from the subject matter of

25 the present invention.

  As mentioned above, the solid-state imaging device
according to the present invention allows to increase

remarkably the dynamic range of amplification type CMOS
image sensors, and to obtain an excellent image without
clipping from small signals to large signals.

   Additionally, the solid-state imaging device
according to the present invention allows to increase
remarkably the dynamic range while performing the
electronic shutter operation in the amplification type
CMOS image sensors, and to obtain an excellent image
without clipping from small signals to large signals.

   Additional advantages and modifications will
readily occur to those skilled in the art. Therefore,
the invention in its broader aspects is not limited to
the specific details and representative embodiments
shown and described herein. Accordingly, various
modifications may be made without departing from the
spirit or scope of the general inventive concept as
defined by the appended claims and their equivalents.